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Journal of Applied Physics Welcomes New Editor-in-Chief André Anders

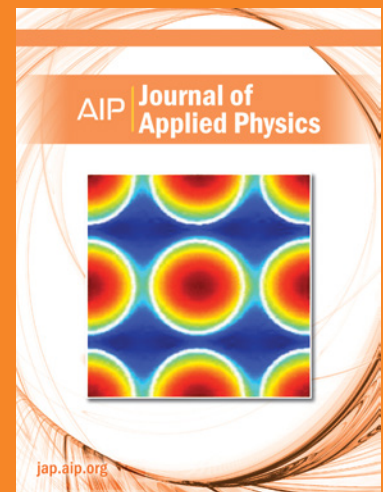
Lawrence Berkeley National Laboratory

Dr. Anders earned his Ph.D. in physics at Humboldt University Berlin, Germany in 1987. Following appointments as Staff Scientist at the Central Institute for Electron Physics (The Academy of Sciences) in (East) Berlin, Germany, and the Max Planck Institute for Plasma Physics in Garching, Germany, Dr. Anders joined Lawrence Berkeley National Laboratory (LBNL) in Berkeley, California, in 1992. Currently holding the prestigious position of Senior Scientist and Leader of the Plasma Applications Group at LBNL, Dr. Anders' research focuses on plasma physics and materials science. Furthermore he has served as Associate Editor of *Journal of Applied Physics* since 2009.

Throughout his career, Dr. Anders has been the recipient of numerous prestigious awards, including:

- Walter Dyke Award, the highest award of the International Symposia of Electrical Discharges and Insulation in Vacuum (2014)
- Mentor Award of the Society of Vacuum Coaters (2011)
- IEEE Merit Award of the IEEE Nuclear and Plasma Sciences Society (2010)
- Chatterton Award (1994)
- R&D 100 Award for the development of the Constricted Plasma Source (1997)
- R&D 100 Award for developing pulsed filtered arc technology for deposition of ultrathin films of diamond-like carbon on read-write heads for computer hard disks (2009)

Dr. Anders is also a prolific contributor to the literature with more than 300 peer-reviewed journal articles and three books to his credit. He is an active member of several conference program committees and is a Fellow of several professional societies.



This influential international journal publishes significant new experimental and theoretical results of applied physics research. Topics covered are diverse, reflecting the most current applied physics research, and include areas of particular emerging interest. It is the most highly cited journal in Applied Physics publishing full-length articles (Thomson Reuters 2013).

Stay tuned for news about exciting changes to JAP!

Selected Articles by André Anders:

Effect of duct bias on transport of vacuum arc plasmas through curved magnetic filters

A. Anders, S. Anders, and I. G. Brown
J. Appl. Phys., vol. 75, no. 10, pp. 4900-4905, 1994

Hardness, elastic modulus, and structure of very hard carbon films produced by cathodic-arc deposition with substrate bias

G. M. Pharr, D. L. Callahan, D. McAdams, T.Y. Tsui, S. Anders, A. Anders et al.
Appl. Phys. Lett., vol. 68, no. 6, pp. 779-781, 1996

Ion velocities in vacuum arc plasmas

G. Y. Yushkov, A. Anders, E. M. Oks, and I.G. Brown
J. Appl. Phys., vol. 88, no. 11, pp. 5618-5622, 2000

Ion flux from vacuum arc cathode spots in the absence and presence of magnetic fields

A. Anders, and G. Y. Yushkov
J. Appl. Phys., vol. 91, no. 8, pp. 4824-4832, 2002

High power impulse magnetron sputtering: Current-voltage-time characteristics indicate the onset of sustained self-sputtering

A. Anders, J. Andersson, and A. Ehasarian
J. Appl. Phys., vol. 102, no. 11, pp. 113303-1-11, 2007

Drifting localization of ionization runaway: Unraveling the nature of anomalous transport in high power impulse magnetron sputtering

A. Anders, P. Ni, and A. Rauch
J. Appl. Phys., vol. 111, no. 5, 053304, 2012

Self-organization and self-limitation in high power impulse magnetron sputtering

A. Anders
Appl. Phys. Lett., vol. 100, no. 22, 224104, 2012

Plasma potential mapping of high power impulse magnetron sputtering discharges

A. Rauch, R. J. Mendelsberg, J. M. Sanders and A. Anders
J. Appl. Phys., vol. 111, no. 8, 083302, 2012

Drifting potential humps in ionization zones: The “propeller blades” of high power impulse magnetron sputtering

A. Anders, M. Panjan, R. Franz, J. Andersson, and P. Ni
Appl. Phys. Lett., vol. 103, no.14, 144103, 2013